

Understanding the frequency dependence of CV measurements of irradiated silicon detectors

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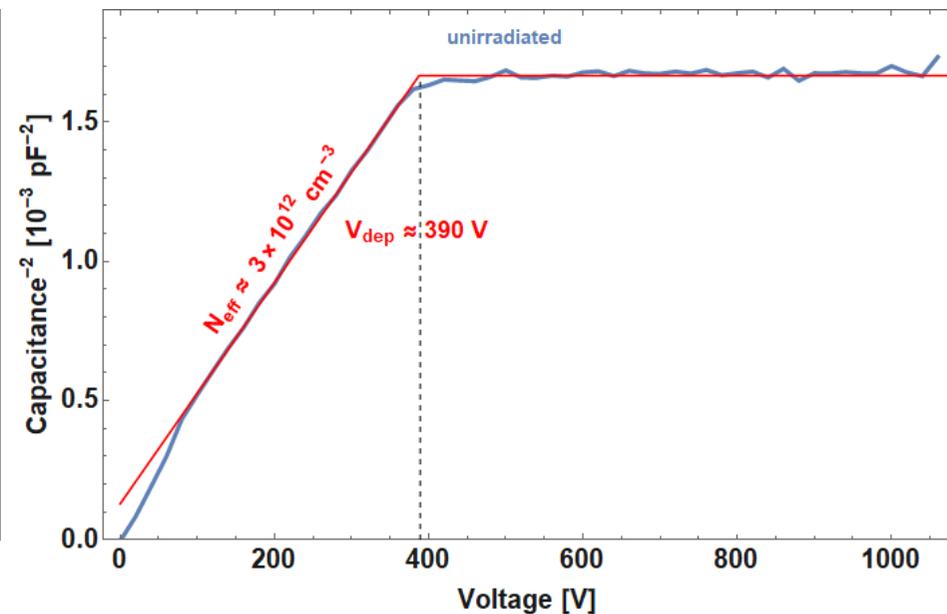
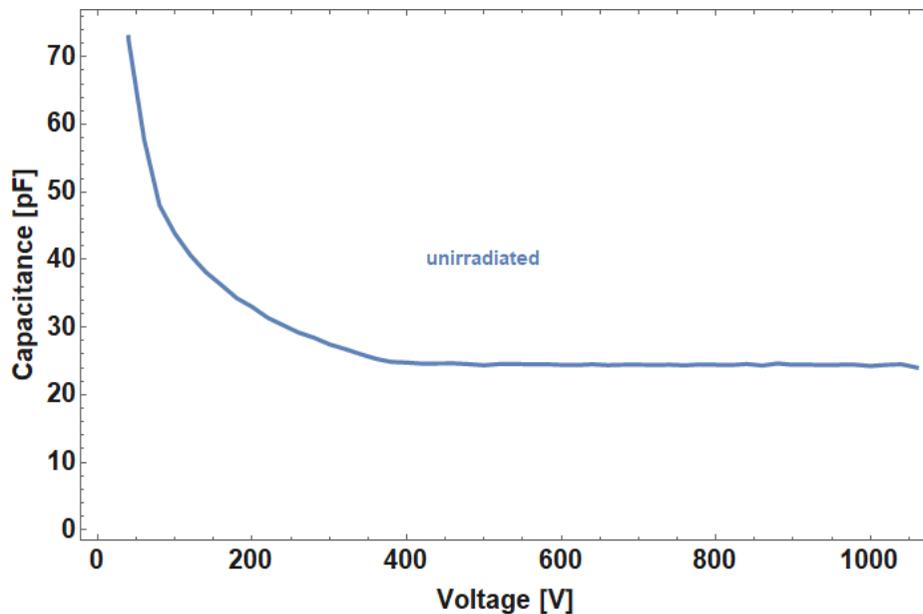
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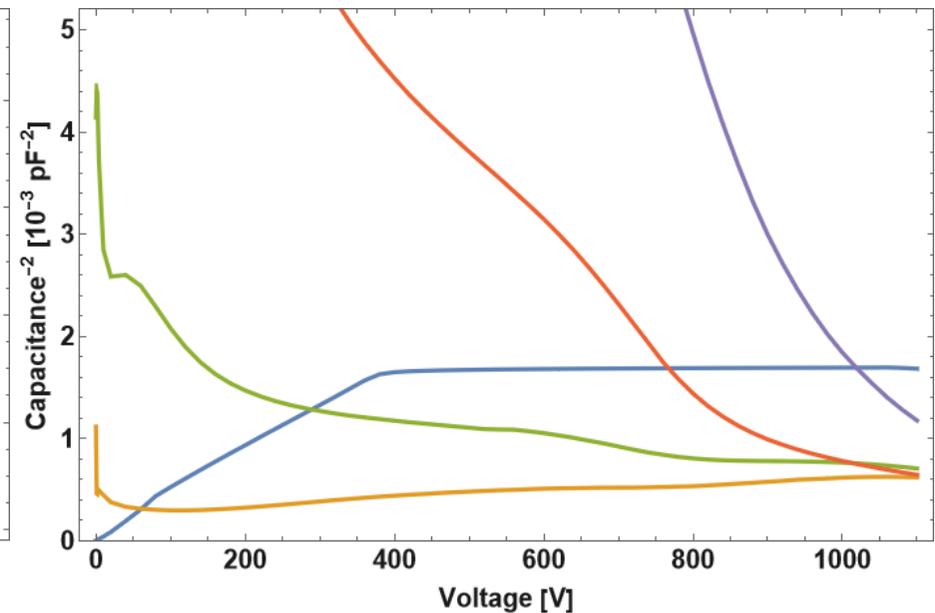
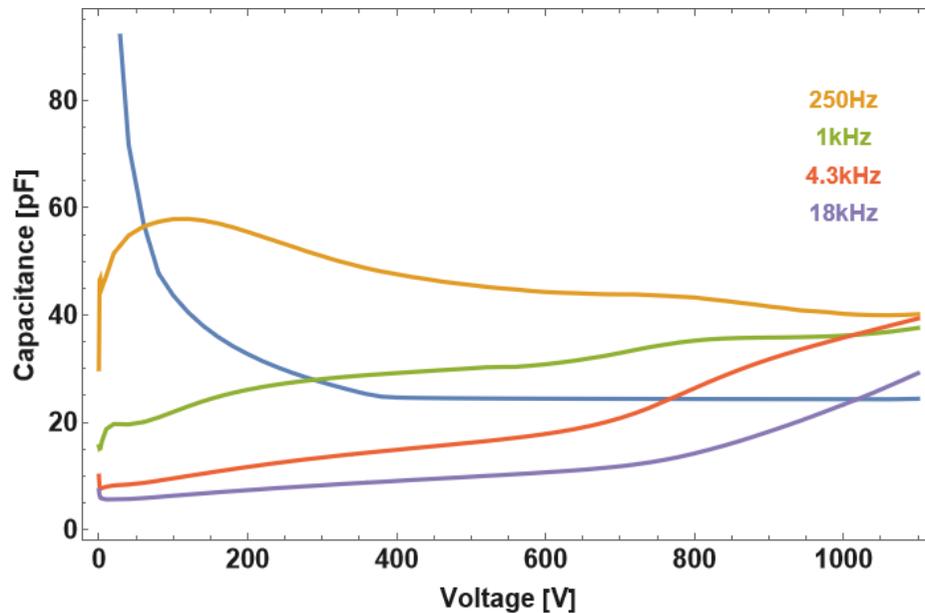
41st RD50 Workshop, Sevilla

- ▶ Capacitance vs. Voltage measurements well established for sensor characterisation
- ▶ Capacitance decreases due to increasing depletion
- ▶ When fully depleted, capacitance remains constant
- ▶ Provide doping level and depletion voltage
- ▶ Independent of measurement frequency

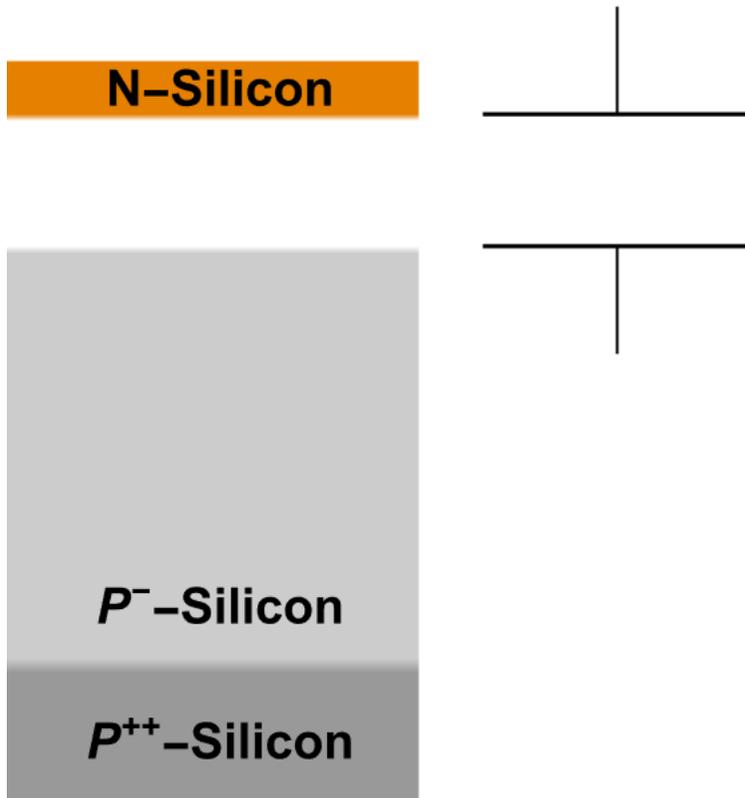


- ▶ Capacitance vs. Voltage measurements well established for sensor characterisation
- ▶ When measuring irradiated devices:
 - ▶ Frequency dependence
 - ▶ Not fittable anymore

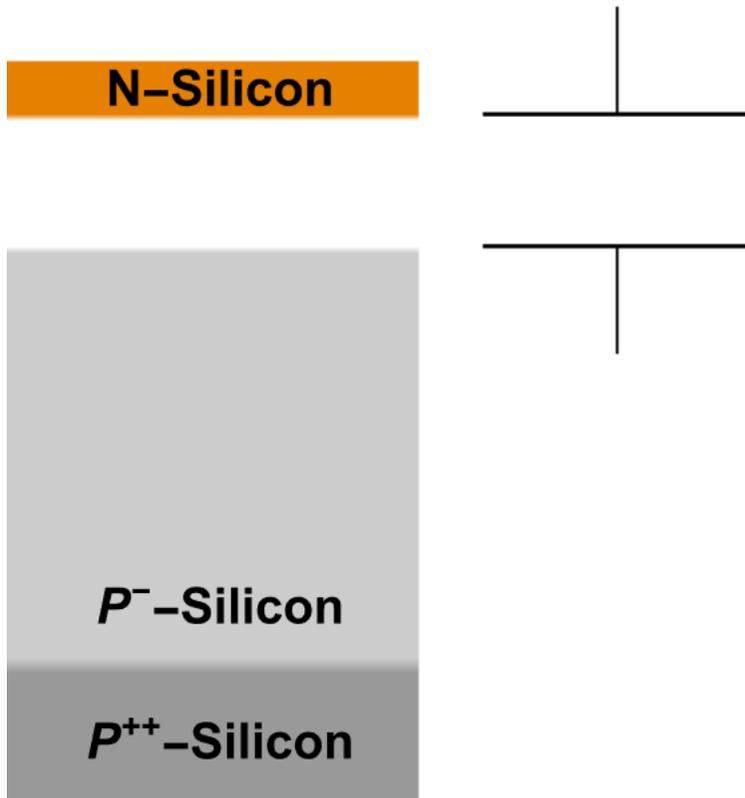
Goal: Understand behaviour and maybe rescue technique



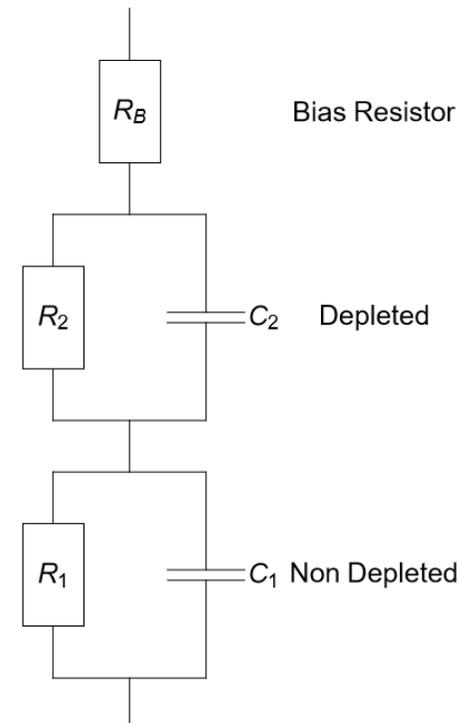
- ▶ Assumptions for resistivity:
 - ▶ Infinite for depleted zone
 - ▶ Zero for all others



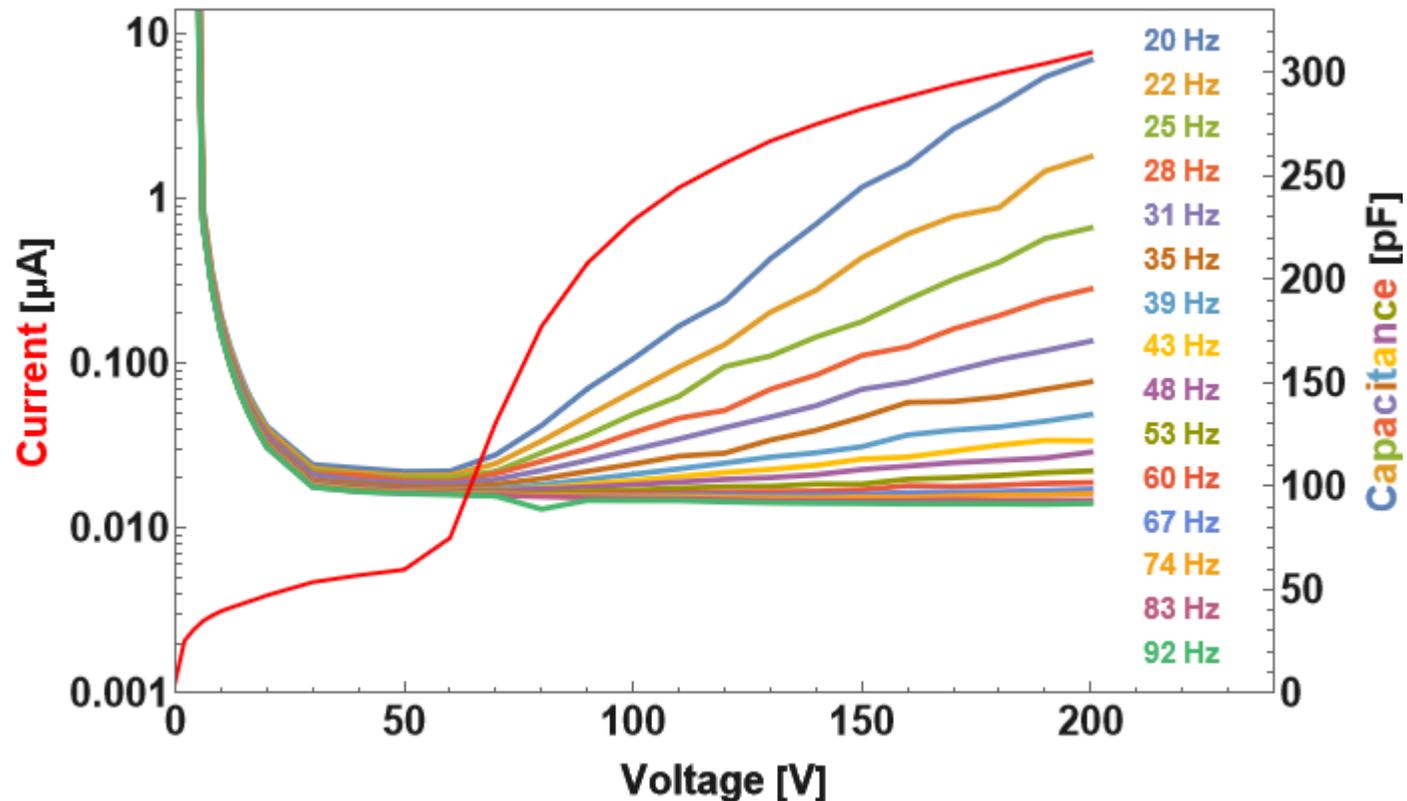
- ▶ Assumptions for resistivity:
 - ▶ Infinite for depleted zone
 - ▶ Zero for all others



- ▶ Modifications for irradiation:
 - ▶ Decrease for depleted zone
 - ▶ Increase for all others
- ▶ Modification for strip detectors:
 - ▶ Introduce bias resistor



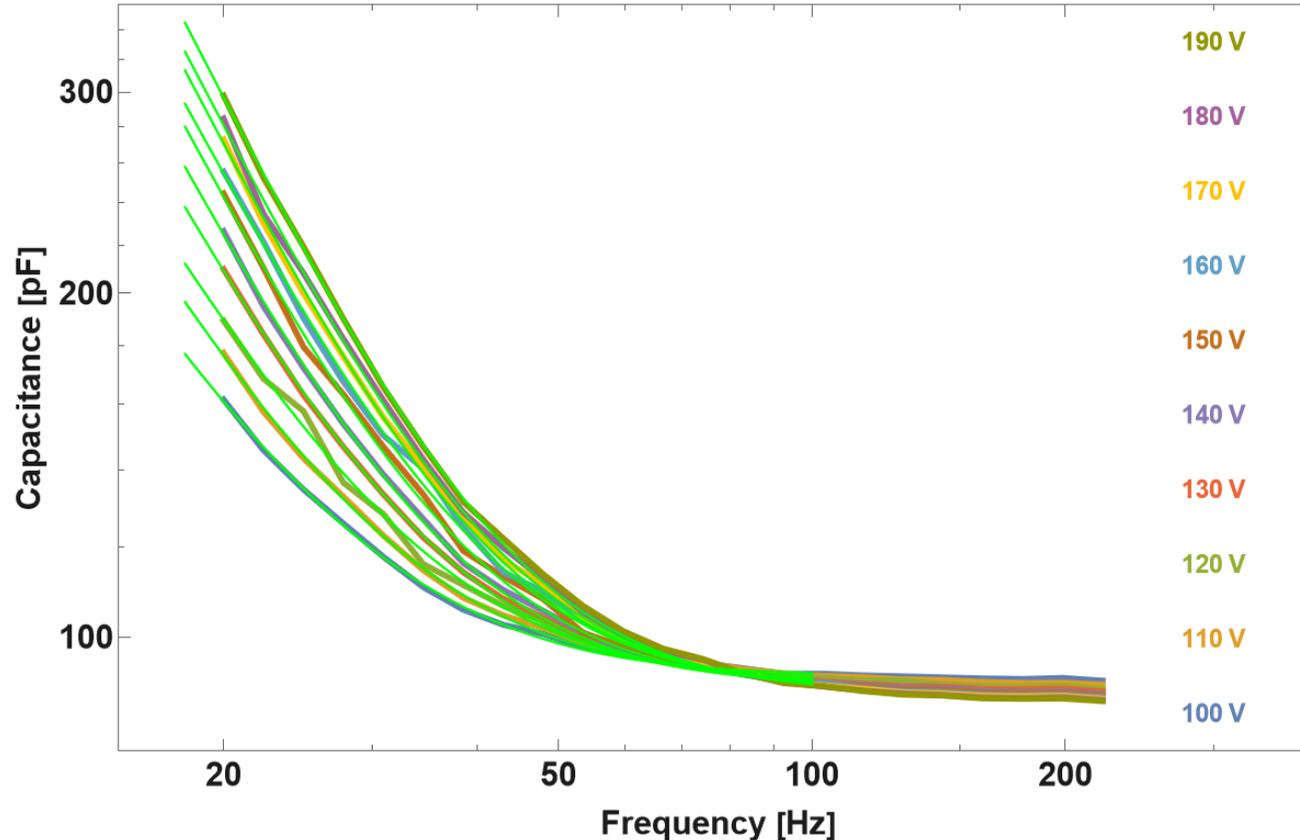
- ▶ For unirradiated sensors:
 - ▶ Capacitance increases when current increases
 - ▶ Only for low frequencies with clear dependency (LF increase)

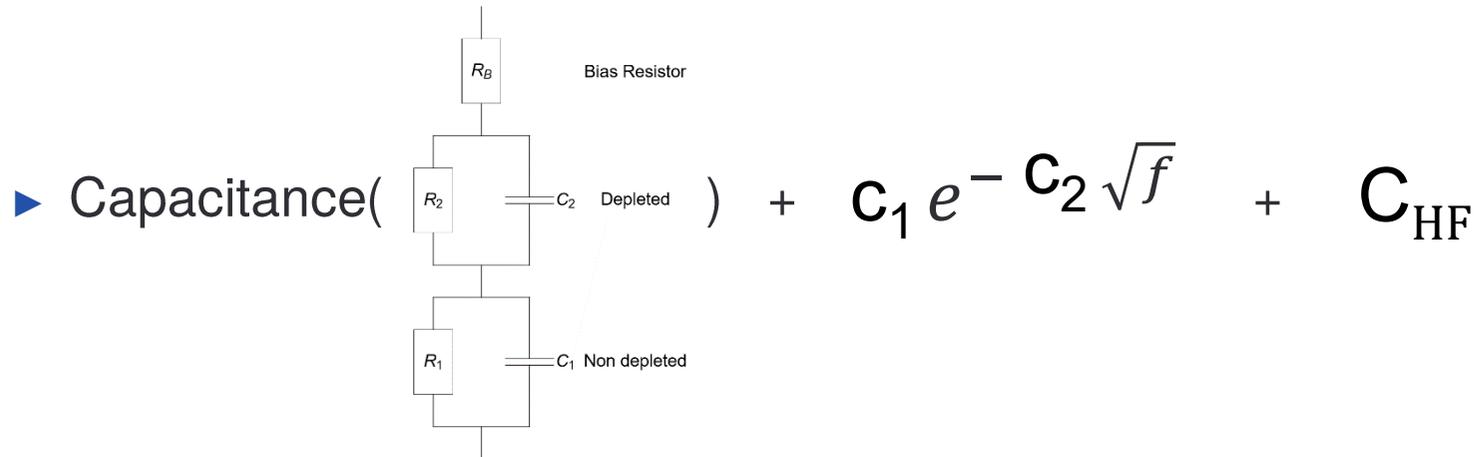


Additional capacitance contribution



- ▶ Frequency dependence perfectly described with: $e^{-\sqrt{f}}$
- ▶ Important: Not representable by any lumped element model
Only broken rational functions possible





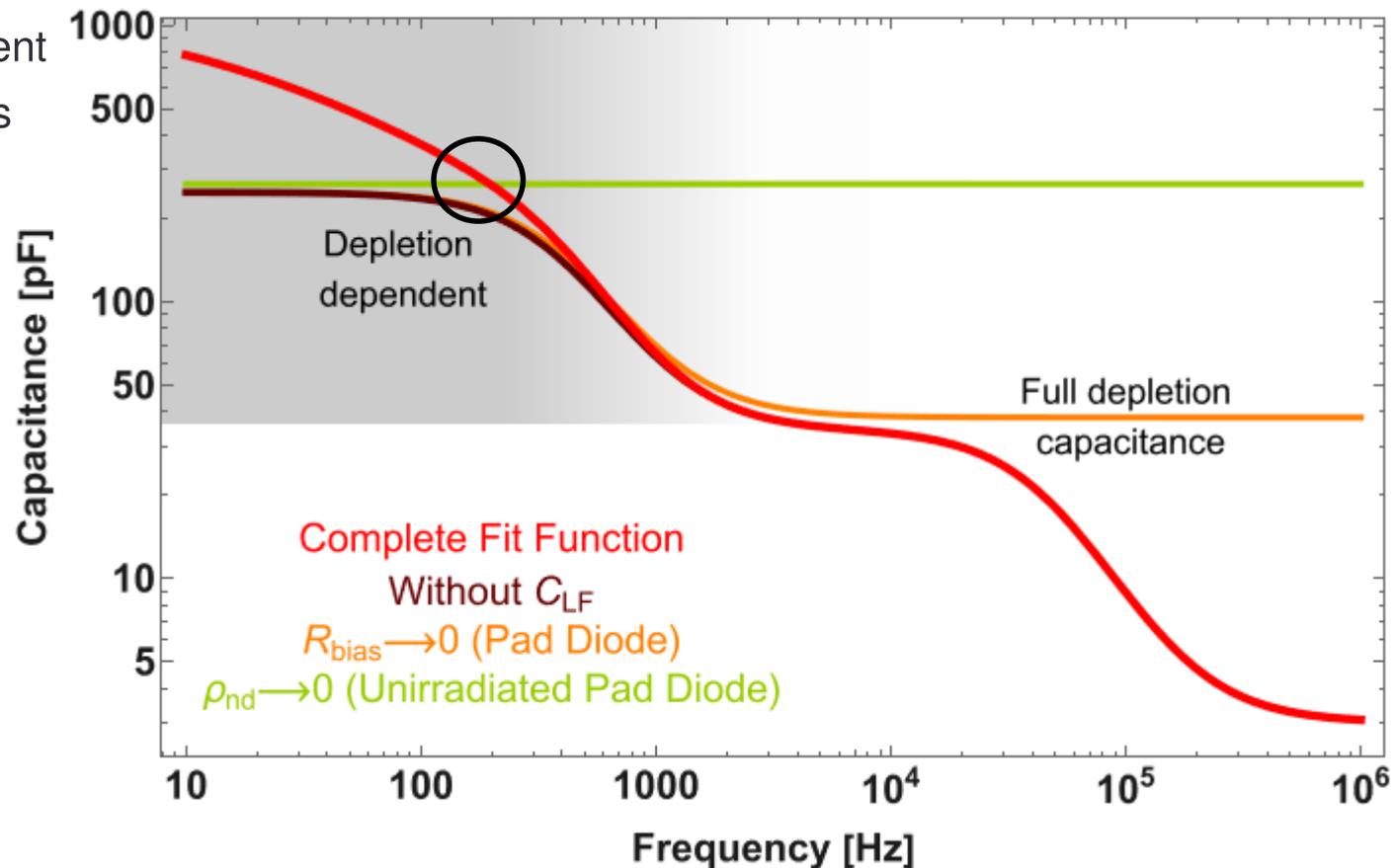
- ▶ Dependent on sensor parameters:
 - ▶ Active area
 - ▶ Thickness
 - ▶ Depletion width
 - ▶ Resistivities of depleted and non depleted zone
- ▶ Same model without HF term works for resistivity

► Capacitance:

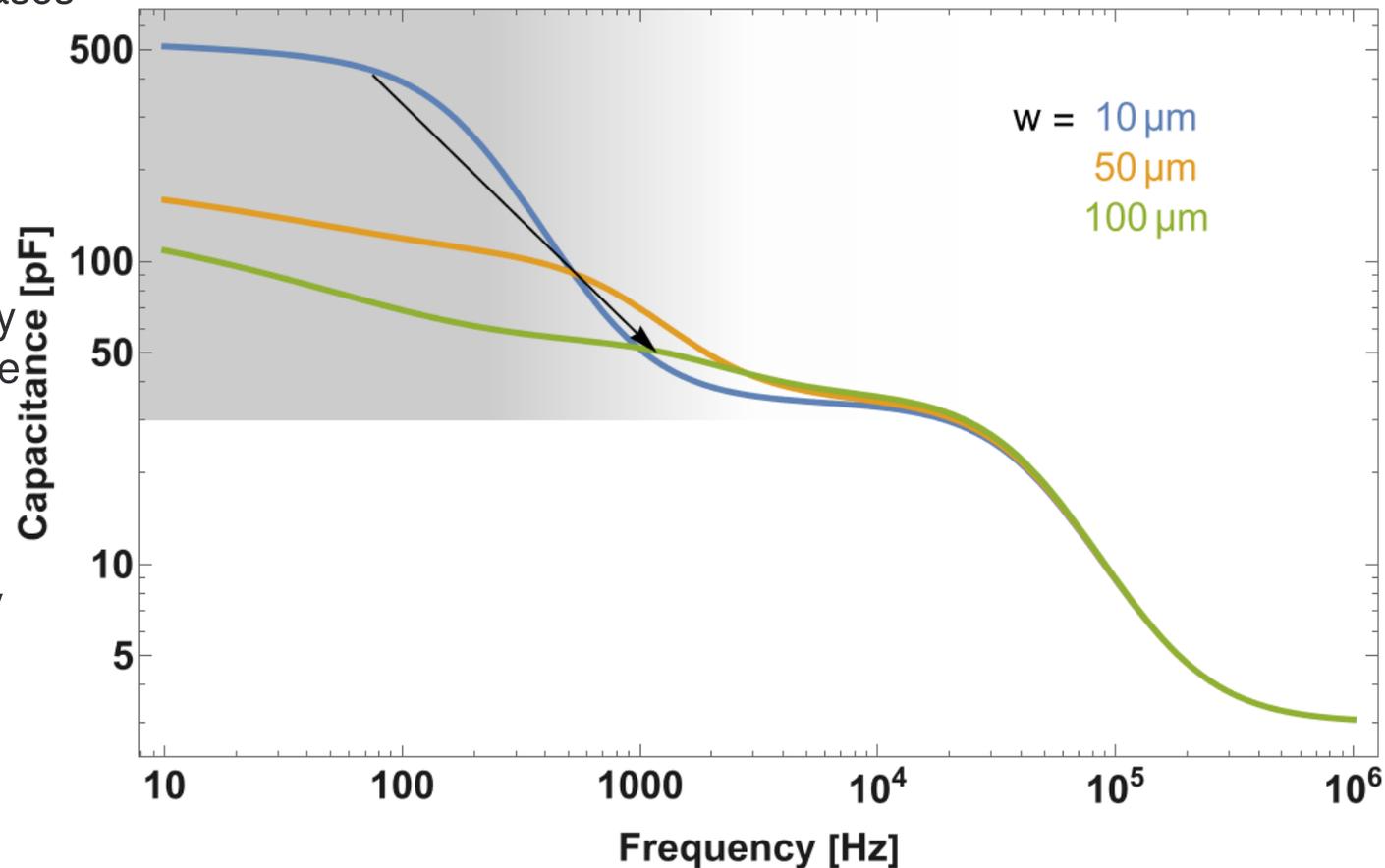
► Depletion dependent for low frequencies

► Intersection of red and green line gives true value

Problem solved?



- ▶ Cut-off frequency shifts to higher frequencies as capacitance decreases
- ▶ Also dependent on sensor parameters
- ▶ No single frequency sufficient for reliable CV measurement
- ▶ But there is an optimum frequency (dependent on the sensor)



Best possible CV result (Diode)

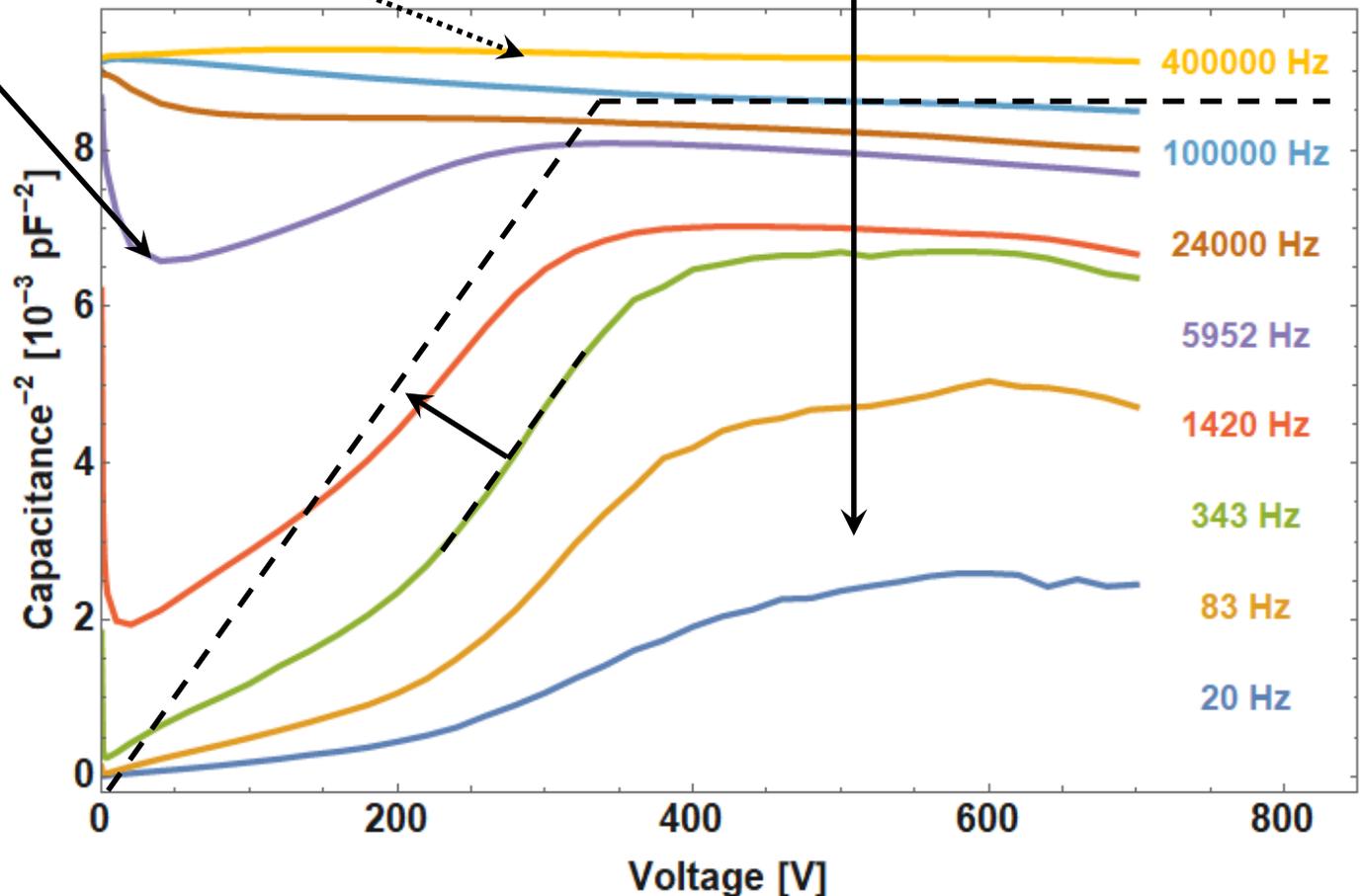


▶ Strip effect would cause further increase from saturation

▶ Shift of cut-off frequency causes offset from zero at low voltages

▶ Find steepest increase and let it begin at the origin. Intersection with plateau is the best estimate for V_{FD} :
(330 ± 15) V

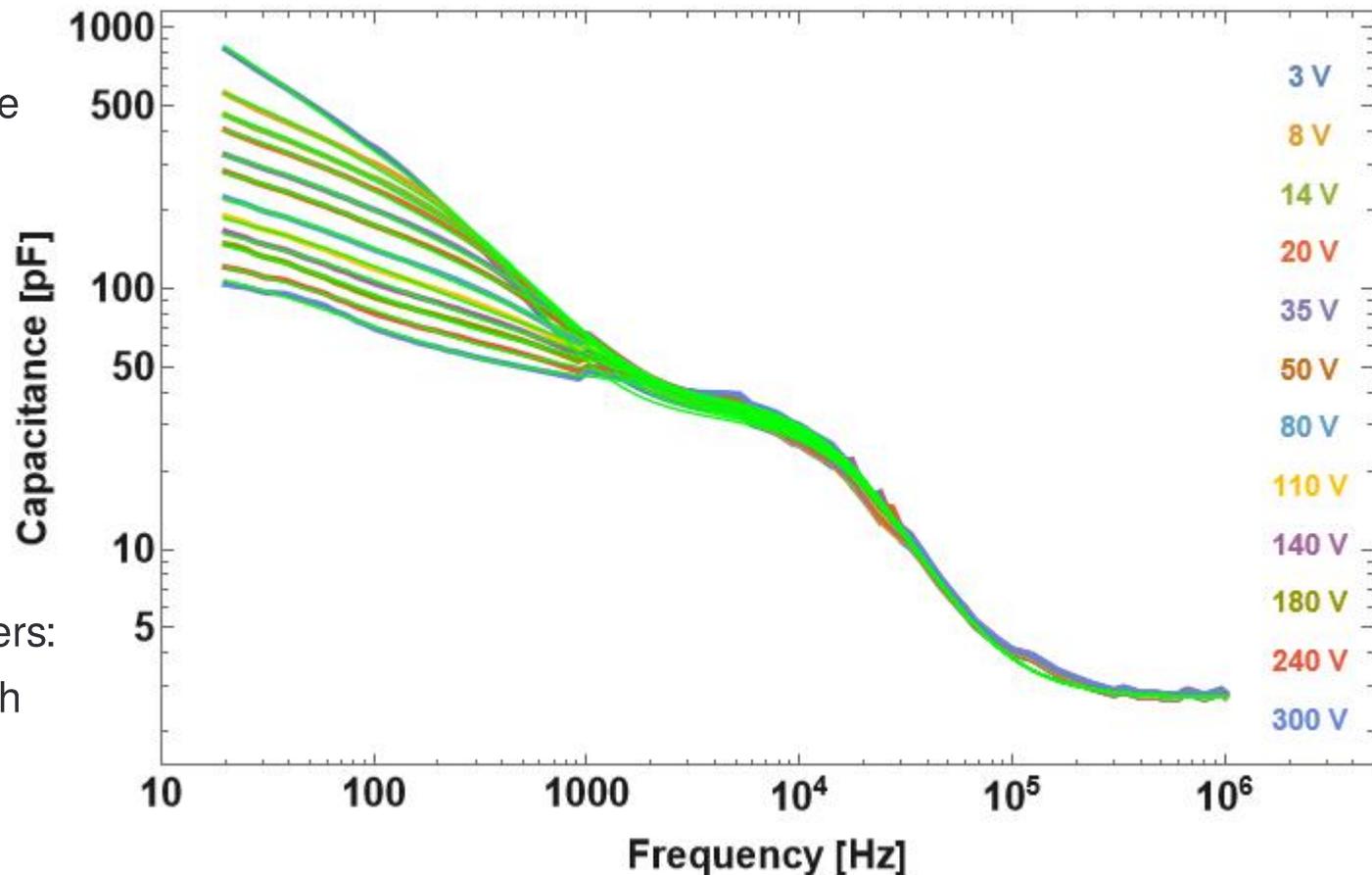
▶ LF increase causes lower saturation level



- ▶ Use of complete model to fit frequency dependent measurements give sensor parameter that can be used for verification:

- ▶ Active area
- ▶ Bias resistance

- ▶ And new parameters:
 - ▶ Depletion width
 - ▶ Bulk resistivity



▶ Active Area

	CMOS	ATLAS R5
Fitted [cm ²]	0.59 ± 0.04	84 ± 3
Reference [cm ²]	$0.63^* \pm 0.05$	$90^{**} \pm 1$

* Calculated from optical inspection

** Calculated from coordinate specs

▶ Bias resistance

	CMOS	ATLAS R5
Fitted [M Ω]	8.2 ± 0.2	1.42 ± 0.12
Reference [M Ω]	$8.7^* \pm 0.2$	$1.5^{**} \pm 0.5$

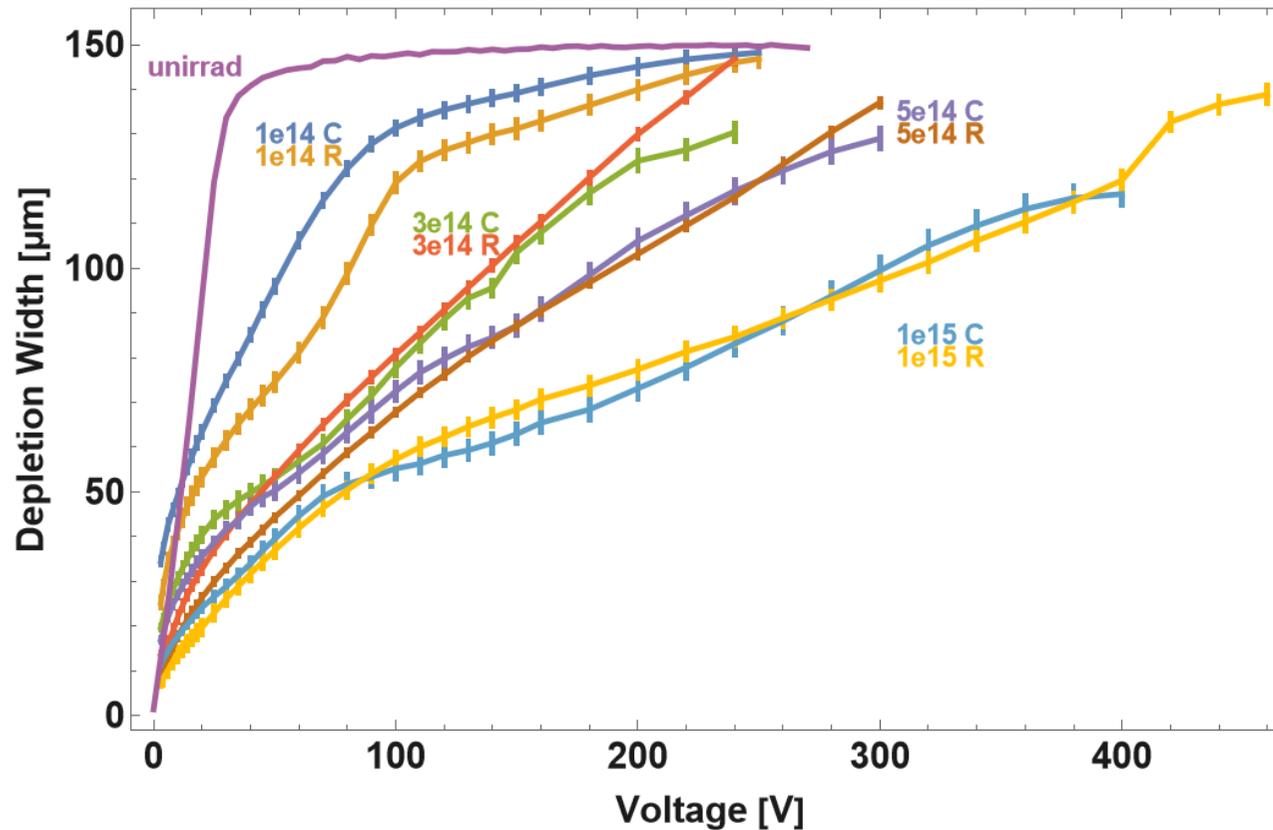
* Measured prior to irradiation

** From Hamamatsu specs

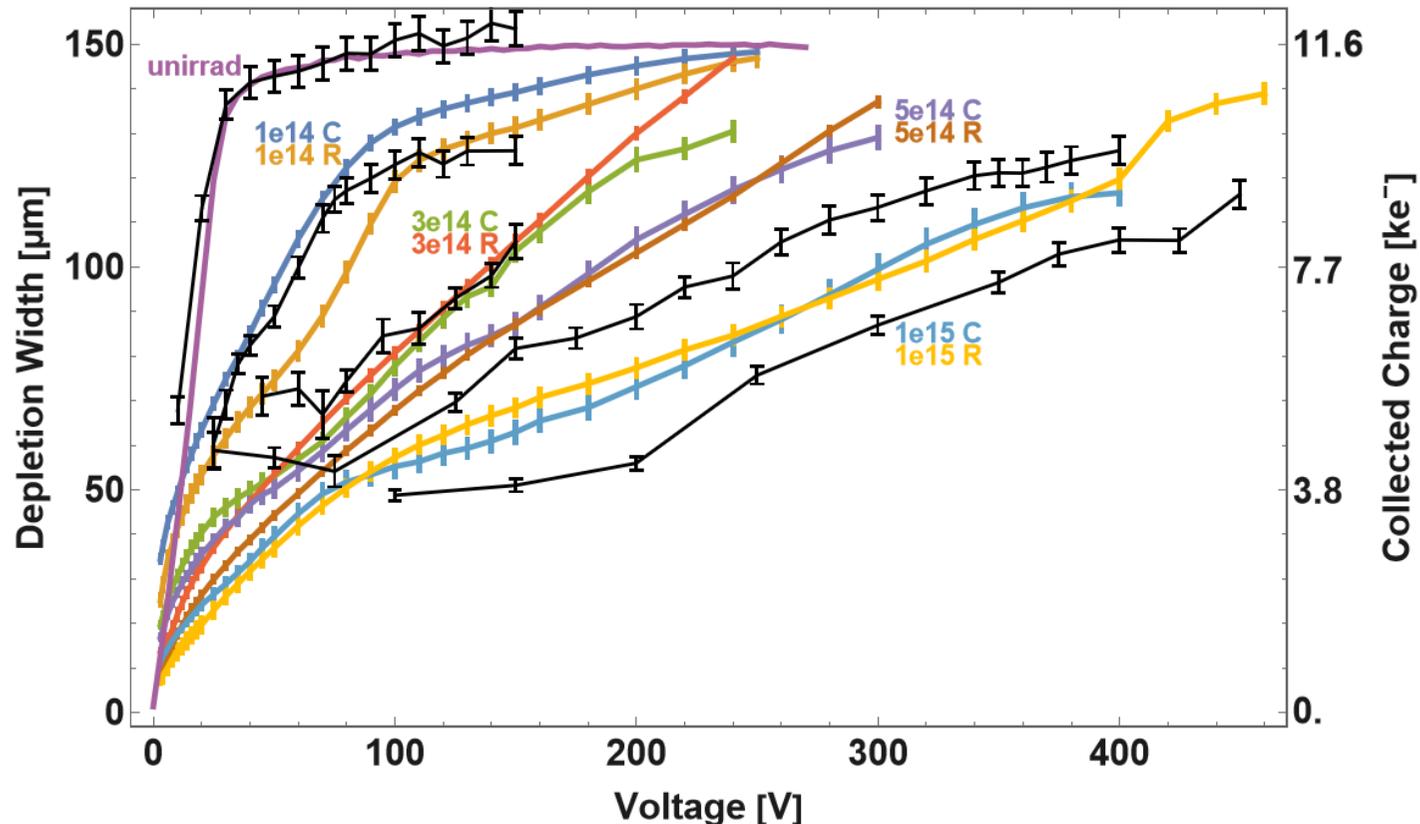
▶ Slightly underestimated

Overall: consistent agreement

- ▶ For CMOS sensors of multiple fluence levels derived from capacitance and resistance measurements

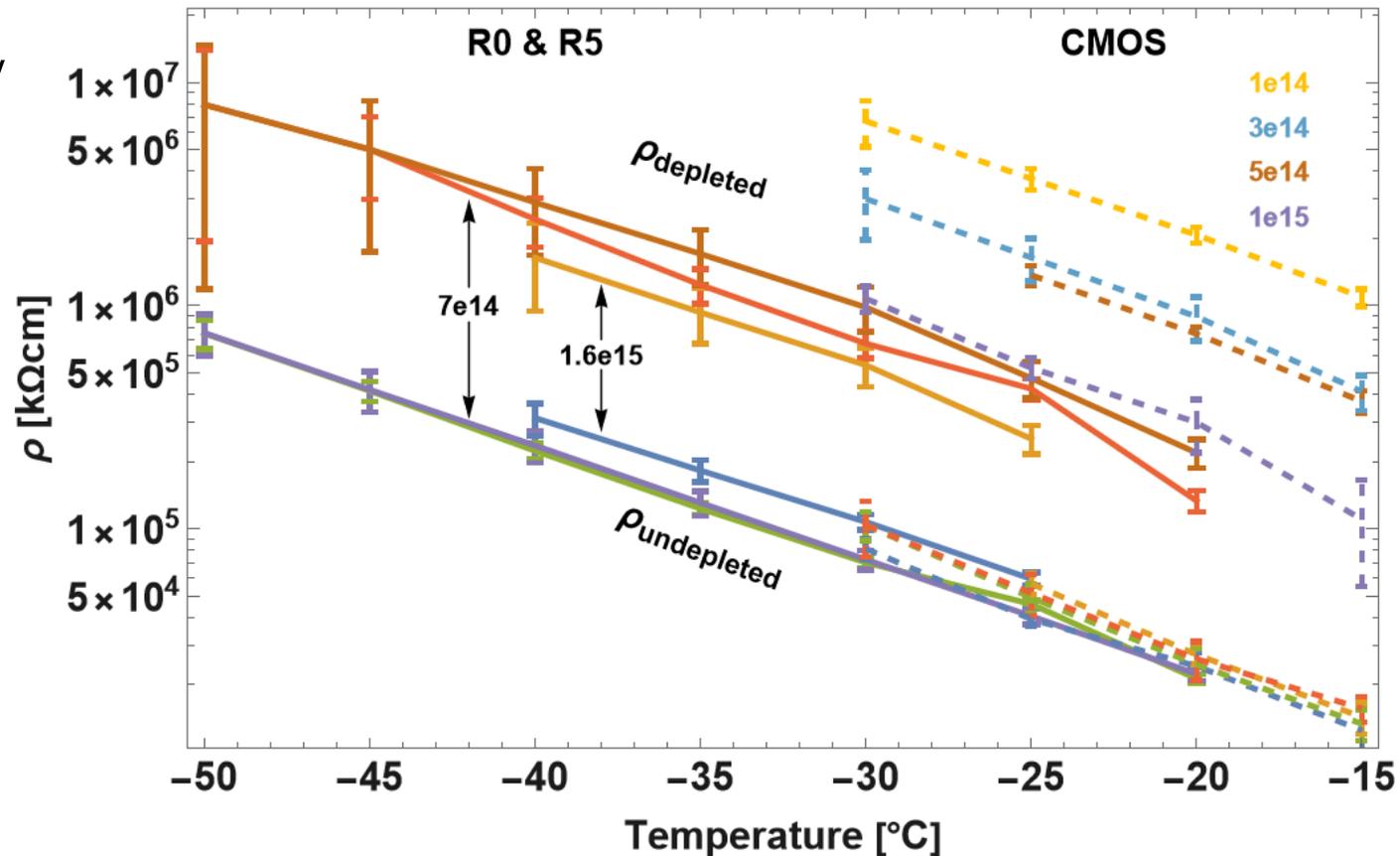


- ▶ For CMOS sensors of multiple fluence levels derived from capacitance and resistance measurements
- ▶ Comparison with charge measurements (AliBaVa):
Disagreement for higher fluences expected due to additional effects (trapping)



- ▶ For depleted and non depleted silicon:
- ▶ Clear temperature signature implies activation energy of (0.60 ± 0.02) eV
- ▶ Fluence dependence only for depleted bulk

- ▶ Annealing also only visible for depleted bulk
- ▶ Magnitudes higher than resistivities according to full depletion voltage:
3.3 – 0.4 kΩcm

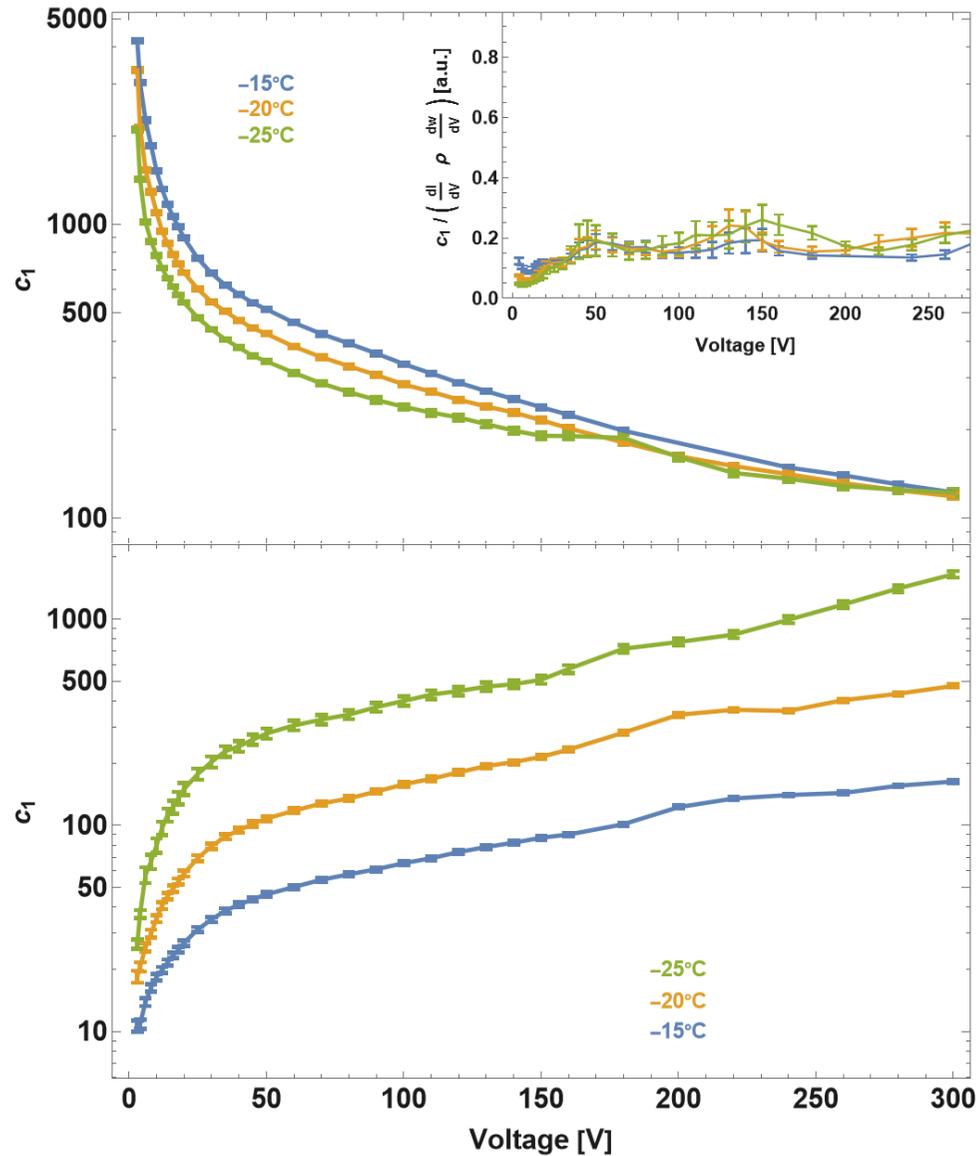


- ▶ New frequency model for CV measurements
 - ▶ Based on complete equivalent circuit
 - ▶ Extended by exponential low frequency term
- ▶ Explanation for frequency dependence of CV measurements
- ▶ Good consistency within verification parameters
- ▶ Realistic orders for depletion width resp. voltage
- ▶ Much larger bulk resistivity than expected from depletion voltage
- ▶ Next step:
 - ▶ Understand the origin of the LF increase



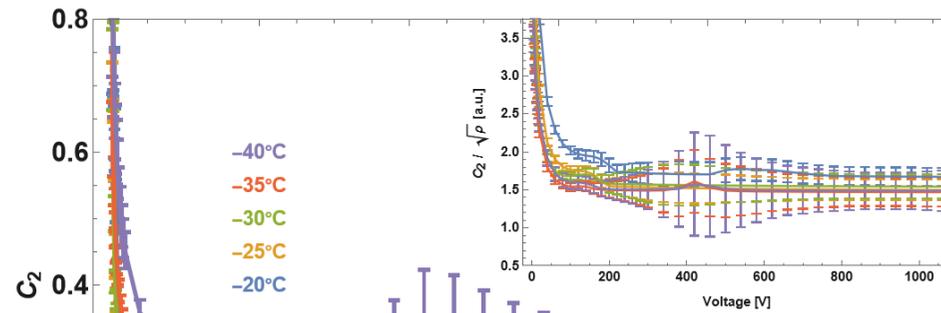
Backup

► For capacitance:

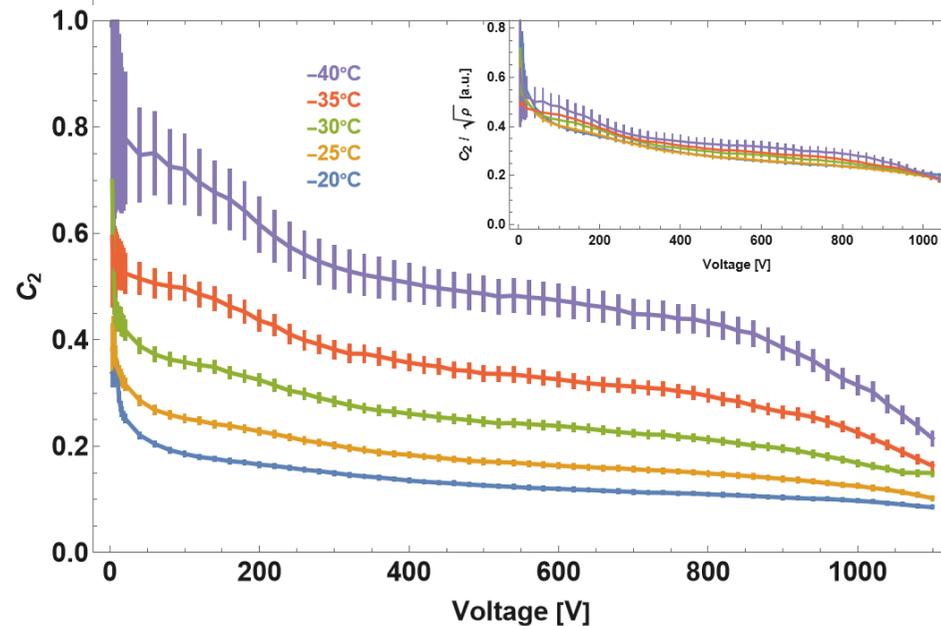


► For resistance:

► For capacitance:



► For resistance:



- ▶ Depletion width of ATLAS R5 sensor prior and after annealing

